

**AMENDMENTS TO THE SPECIFICATION:**

*Please correct the title of the application in the PCT Publication with the English language translation of the specification and insert the following new paragraph:*

METHOD OF FORMING AMORPHOUS SILICA-BASED COATING FILM WITH LOW DIELECTRIC CONSTANT AND THUS OBTAINED SILICA-BASED COATING FILM

**RELATED APPLICATIONS**

The present application is based on International Application No. PCT/JP03/13691 filed October 27, 2003, and claims priority from, Japanese Application Number 2002-318418, filed October 31, 2002, the disclosure of which is hereby incorporated by reference herein in its entirety.

*Please replace paragraph 0124 with the following amended paragraph:*

[ 0124]

5 ml of the coating liquid for forming a coating film (Example of coating liquids ①-2) obtained Example 1 was applied on a silicon substrate with the size of 8 x 8 square inches using the spin coat method under the same conditions as those employed in Example 1.